

Experimental details

Synthesis of HfO₂ nanoparticles

Hafnium isopropoxide (6.0 g, 12.6 mmoles) was dissolved in 30.0 ml acetic acid and stirred at 65 °C for 15 min to form a clear solution. Then 10.0 ml of a solution comprised of 9.0 ml acetic acid and 1.0 ml H₂O (1.0 g, 55.5 mmoles) was added causing the formation of a white precipitate. The reaction mixture was stirred at 65 °C for 18 h before 10 ml of a similar acetic acid – water solution was added followed by stirring for 3 h at the same temperature. The white precipitate was centrifuged at 8,000 g for 10 min and then washed once with acetic acid and twice with acetone. The final product was dried overnight to give a fine white powder.

Synthesis of (s)-(+)-tetrahydrofurfuryl -O-O'-diacetyl-(2R,3R)-hydrogen tartrate (TDHT)

To a stirred mixture of racemic tetrahydrofurfuryl alcohol (4.7g) and pyridine (0.4 g) solid diacetyl tartaric anhydride (10 g) was added. Stirring was continued for 30 minutes at room temperature, then 5 ml of ethyl acetate was added, and the temperature was raised to 80 °C. After 2 hr heating, 10 ml of ethyl acetate was added, and the mixture was allowed to cool to room temperature, then kept for 10 hrs at 5 °C. The crystals were filtered off, washed with ethyl acetate (10 ml) and dried. 7 g of crude ester was obtained. The crude product was recrystallized three times from ethyl acetate to yield 1.8 g of pure TDHT. IR (KBr, cm⁻¹): ν(C-O): 1069, 1212; ν(C=O): 1750, 1759; ν(CH₃): 2605, 2944; ν(OH): 3495. ¹H NMR (Acetone-d₆): δ 5.74-5.68 (2H, m), 3.62-4.26 (5H, m), 2.09-2.17 (6H, s), 1.18-2.08 (4H, m) ppm.

Ligand exchange reaction and purification

HfO₂-acetate x (x=0.04~0.12g) was mixed with ligand 0.2 g + 1 ml of PGMEA in 25 ml round flask. After ultra-sonication of the solution for 5 minutes, the cloudy solution was heated at 130 °C for 10 minutes. After ligand exchange, the solution became clear. To eliminate any residue of acetate or acetic acid, an excess of acetone/water/ether co-solvent was added to the solution. The solution was centrifuged at 10,000 rpm for 10 min, and then washed three times with a mixture of acetone/water/ether. The residual powder was redissolved in water/acetone (50/50) mixture. The solution was purified by dialysis using semipermeable membrane (molecular cutt off, 500) for 3 days and vacuum dried at 50 °C.

Film preparation

193 nm photoresist powder poly(methyladamantane methacrylate-*co*-alpha-methacryloxy-gamma-butyrolactone) (PMAdMA-*co*-GBLMA) (Mitsubishi Rayon America, Inc.) 50 mg and photoacid generator (PAG) triphenylsulfonium triflate 2.5 mg were dissolved in 1 ml of PGMEA. A desired amount of HfO₂-TDHT is added to the photoresist solution. After sonication and heat treatment, the solution became transparent. After being filtered through 0.2 µm syringe filter, the solution was spin-coated onto 2 inch BARC-coated or HMDS primed Si wafers at 2000 rpm for 60 s. The film was baked at 130 °C for 60 s after spin coating to remove residual solvent in the film. The BARC-coated Si wafer (~90 nm thickness) was supplied by SEMATECH (ARC29A-8) and was baked at 120 °C for 60 s for the dehydration and was cooled to room temperature prior to resist coating. The film thickness and the roughness of each film are listed in table S1.

HfO ₂ -TDHT content in PMAdMA- <i>co</i> -GBLMA	Film thickness (nm)	Roughness (nm)
0%	130±16	0.287±0.005
4%	180±10	0.276±0.004
8%	210±7	0.539±0.013
12%	220±8	0.485±0.022

Table S1. Film thickness and roughness of PMAdMa-*co*-GBLAMA + HfO₂-TDHT film after spin-coated at 2000 rpm for 60 s on BARC coated film.

Lithographic Evaluation

Deep-UV patterning was done by exposing films through a quartz mask using an ABM mask aligner at a wavelength of 254 nm (measured power 8.7 mW/cm²). High-resolution patterning was done using a Leica VB6-HR electron-beam lithography system operating at 100 kV, followed by a post-exposure bake of 115 °C for 60 sec.

Supporting figures

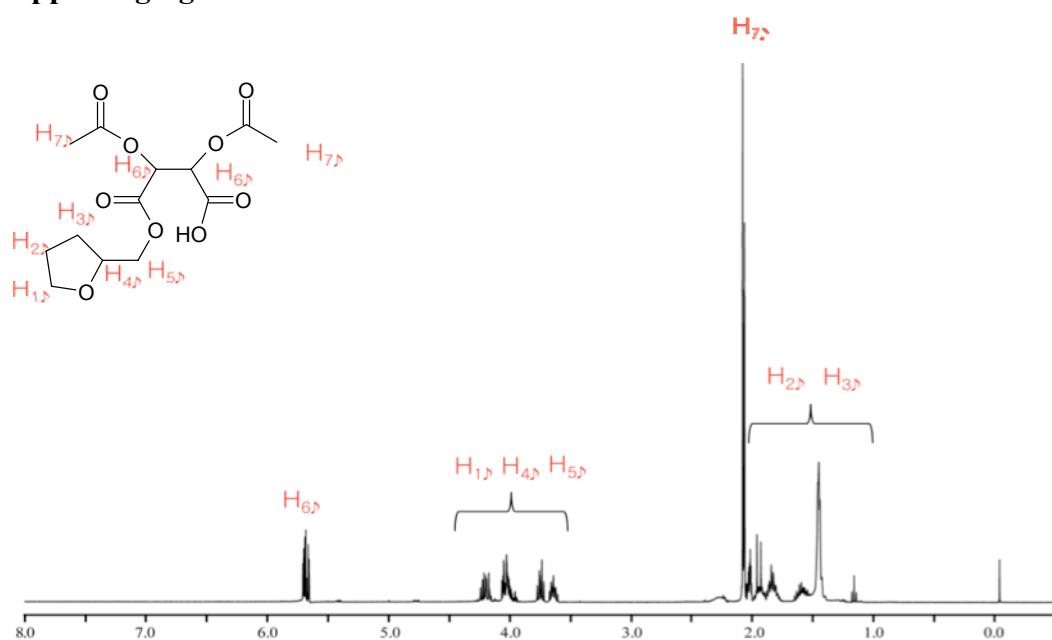


Figure S1. ^1H NMR spectrum of TDHT

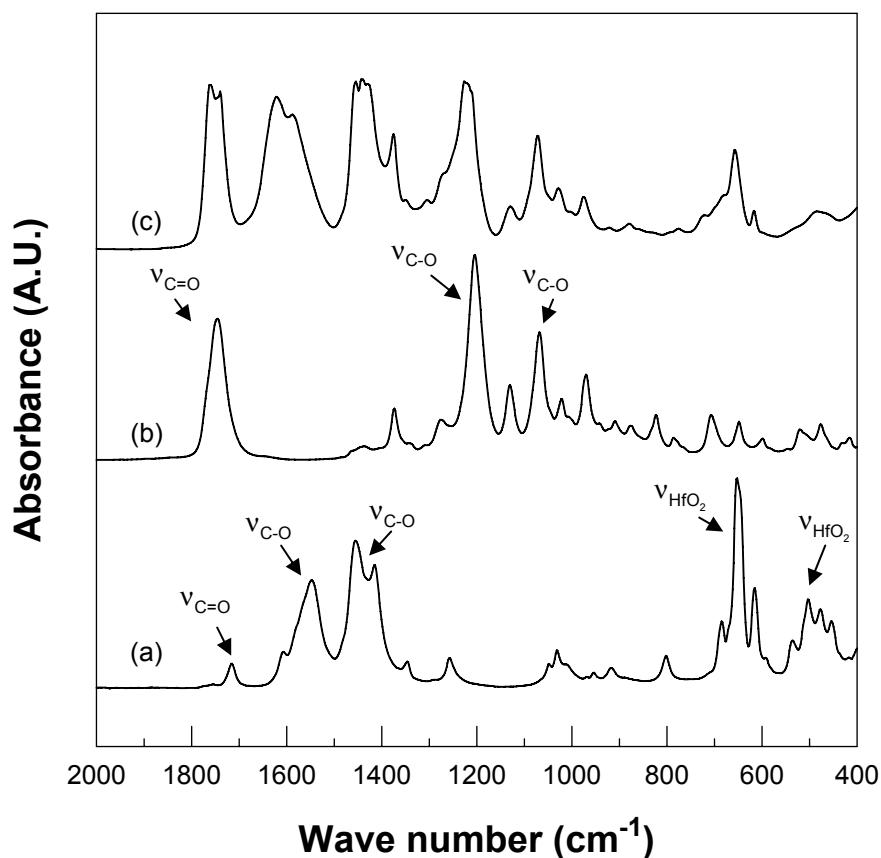


Figure S2. FTIR spectra of (a) HfO₂-acetate, (b) TDHT, (c) HfO₂-TDHT

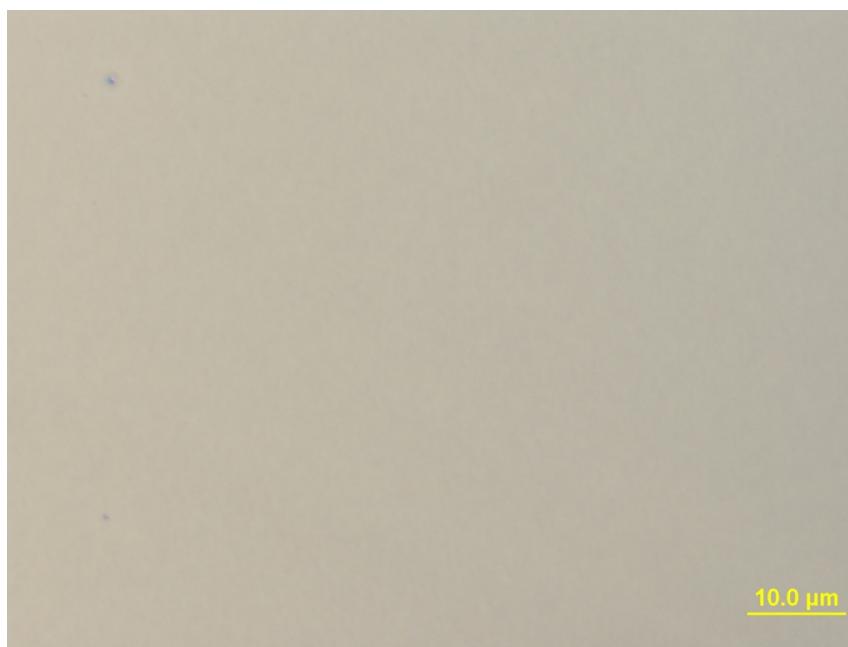


Figure S3. Optical micrograph of P(MAdMA-*co*-GBLMA)/ HfO₂-TDHT nanoparticles (8 wt%).

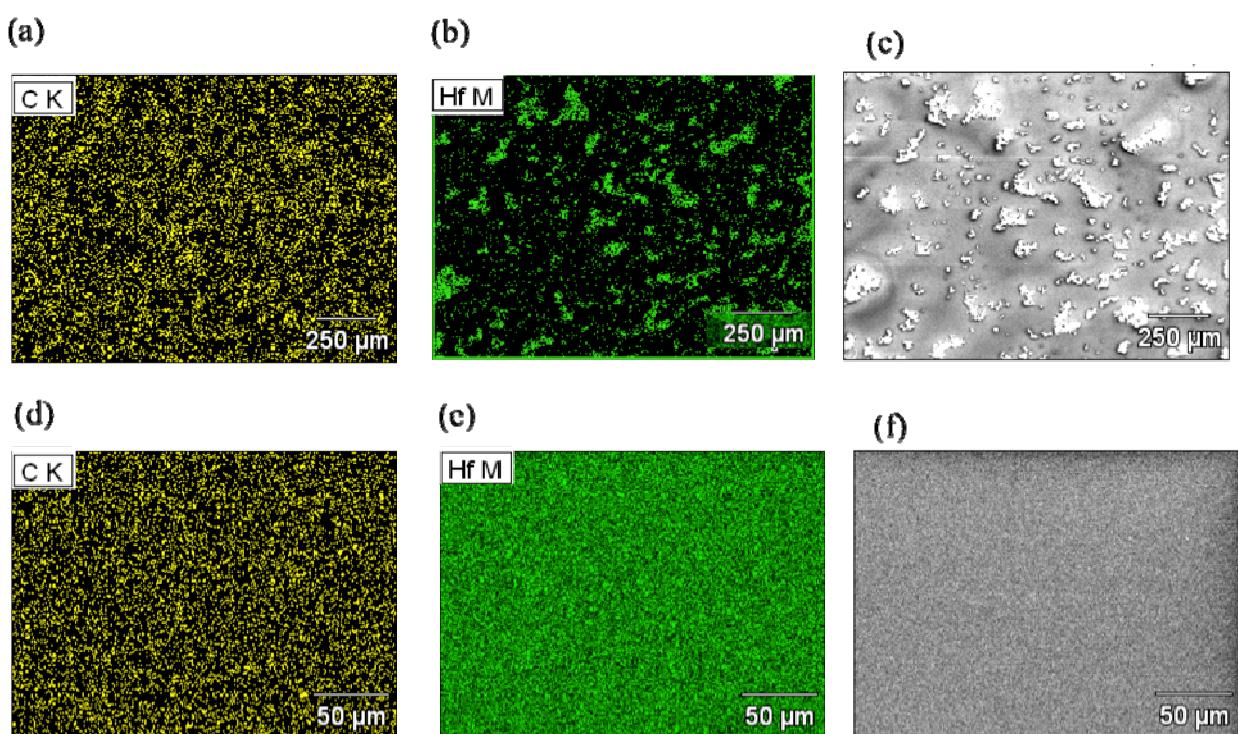


Figure S4. SEM images of (c) P(MAdMA-*co*-GBLMA)/ HfO₂-acetate (8wt%) and (f) P(MAdMA-*co*-GBLMA)/ HfO₂-TDHT (8wt%) and corresponding elemental maps (a), (d) C at K peak and (b), (e) Hf at M peak.

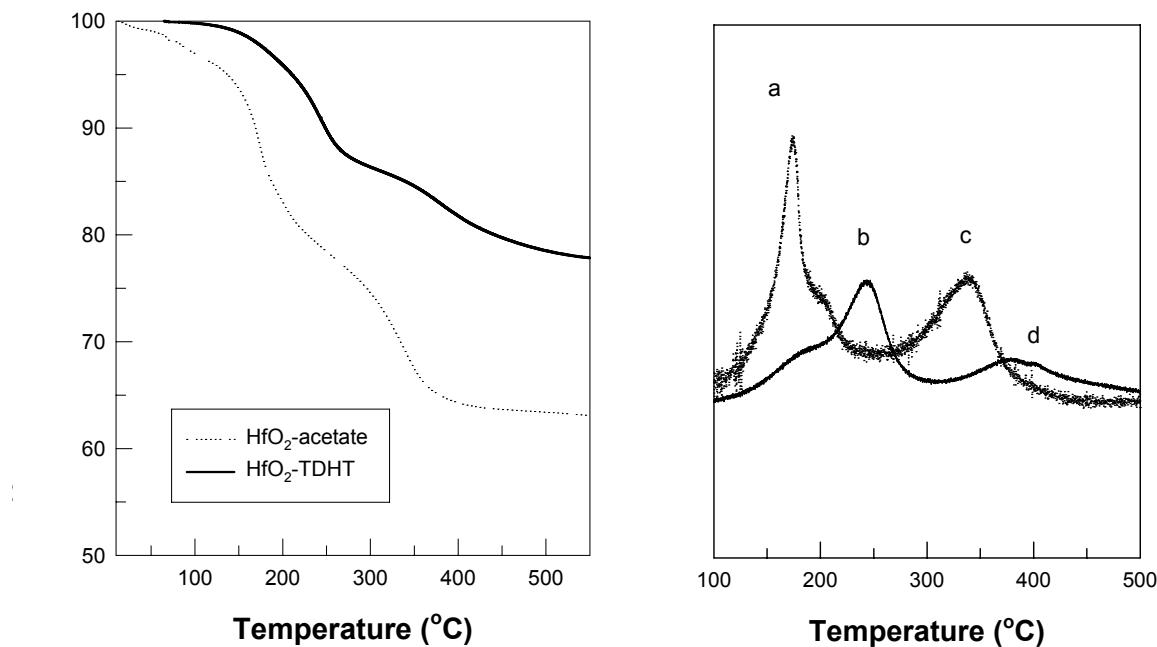


Figure S5. TGA thermogram for HfO₂-acetate and HfO₂-TDHT (left) and 1st derivative curve of the left graph (right). The peak a is attributed to the disconnection of crystal water and the shoulder next to the peak a is related with the reaction: CH₃COO → CO₂ + solid residue.^{S1} The peak b is related with the dissociation of TDHT group. The Peak c and d are attributed to the decomposition of organic residue.

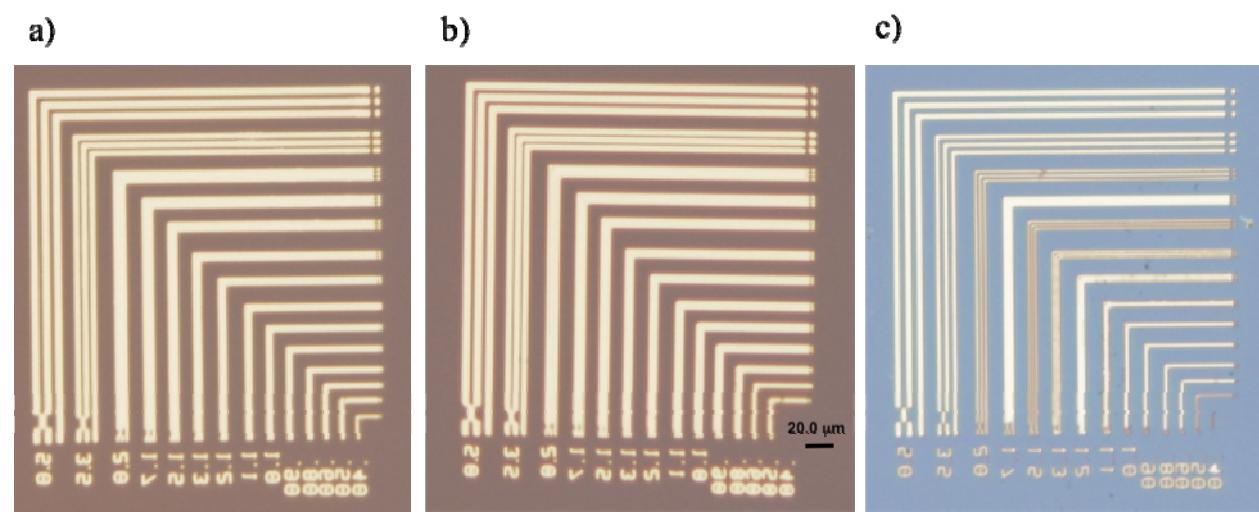


Figure S6. Optical microscopy images of (a) P(MAdMA-*co*-GBLMA), (b) P(MAdMA-*co*-GBLMA)/ HfO₂-TDHT nanoparticles (8 wt%) and (c) P(MAdMA-*co*-GBLMA)/HfO₂-TDHT nanoparticles (12 wt%), patterned by DUV contact aligner.

References

- S1 A. Bakalova, *J. Therm. Anal. Cal.* 2009, **2**, 593.